New chapters on International Registrations/Subsequent Designations Designating Singapore, International Applications Where Singapore Is the Office of Origin

As part of IPOS' ongoing effort to provide greater clarity to applicants in relation to the handling of (i) International Applications designating Singapore via the Madrid system and (ii) International Applications with Singapore as the Office of Origin, two new chapters have been introduced to the Trade Marks Work Manual.

The chapters explain the procedures and work practices relating to these applications, and cover changes made to the International Registrations.

To view the new chapter on International Registrations/Subsequent Designations Designating Singapore, please click here.

To view the new chapter on International Applications Where Singapore Is the Office of Origin, please click here.

Revisions to the Existing Chapter on Shape Marks

In light of the recent developments in this area, we have reviewed our examination practices and updated the chapter on Shape Marks in the Trade Marks Work Manual.

To view the updated chapter on Shape Marks, please click here.

Revisions to the Existing Chapter on Relative Grounds for Refusal of Registration

To provide greater clarity and guidance to applicants in relation to overcoming relative grounds of refusal through filing evidence to indicate honest concurrent use, the Registry has reviewed and updated the relevant chapter in the Trade Marks Work Manual.

Consequent amendments were also made to Appendix 1: Filing evidence of use of a trade mark in the chapter on Evidence of Distinctiveness Acquired Through Use, to consolidate the examination practice in respect of filing evidence to indicate honest concurrent use in the chapter on Relative Grounds for Refusal of Registration.

To view the updated chapter on Relative Grounds for Refusal of Registration, please click here.

To view the updated chapter on Evidence of Distinctiveness Acquired Through Use, please click here.